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Substitute Specification

Application No. 10/717,545

TITLE OF THE INVENTION

**EXPOSURE APPARATUS INCLUDING A READ CIRCUIT FOR
READING ELECTRICAL SIGNALS FROM A PLURALITY OF PHOTOELECTRIC
CONVERTERS**

FIELD OF THE INVENTION

[0001] The present invention relates to an exposure apparatus suitable for manufacturing a device such as a semiconductor device or liquid crystal display device.

BACKGROUND OF THE INVENTION

[0002] An exposure apparatus which transfers the pattern of a master such as a reticle onto a photosensitive material applied to a substrate such as a wafer or glass plate is used to manufacture a device such as a semiconductor device or liquid crystal display device by photolithography.

[0003] In general, a photosensitive material applied to a wafer has a predetermined proper exposure amount. In a conventional exposure apparatus, a beam splitter is arranged in an illumination optical system for illumination light. The light quantity of part of the illumination light split by the beam splitter is monitored by a photoelectric sensor (integrated exposure amount sensor), thereby indirectly monitoring the exposure amount of the wafer.